

ENHANCEMENT OF FABRICATION YIELDS OF NANOMECHANICAL DEVICES BY THIN FILM DEPOSITION

ABSTRACT

A protective film is applied onto a nanostructural feature
5 supported on a sacrificial layer by energy beam assisted deposit of
material from a vapor through which the beam passes. A wet etchant is
applied to etch away the sacrificial layer beneath the nanostructural
feature to leave it suspended as a cantilever or bridge. The film protects
the structural feature from damage during etching, and may be removed
10 after the wet etching process is completed.